

# Sensitivity analysis and tolerancing of Mid Wave IR metalenses

Lieven Penninck, Wouter Woestenborghs

OSA Topical Meeting on Flat Optics, June 29 2021, Virtual Event



**PlanOpSim**

Enlightened Planar Optics  
WWW.PLANOPSIM.COM

# Who are we?

- ❖ Start-up from Ghent, Belgium
- ❖ Dedicated provider of:
  - **Simulation** software for **metasurfaces**
  - **Designhouse** for photonic & optical applications
- ❖ 20 years of photonics R&D experience in industry and academia:
  - Simulation
  - Fabrication
  - Measurement
- ❖ Supported by:



AGENTSCHAP  
INNOVEREN &  
ONDERNEMEN



## Founding team

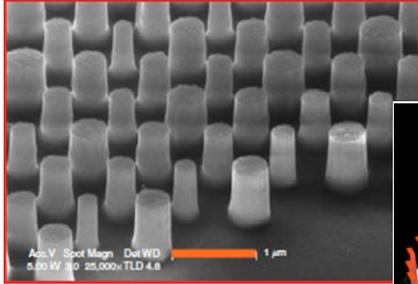


Dr. Lieven  
Penninck

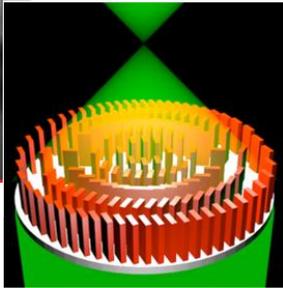


Dr. Wouter  
Woestenborghs

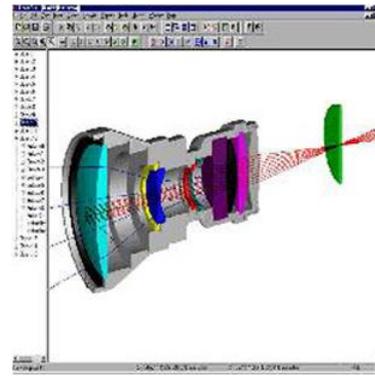
Nano-scale design



Component design



System Integration



## Planopsim's mission

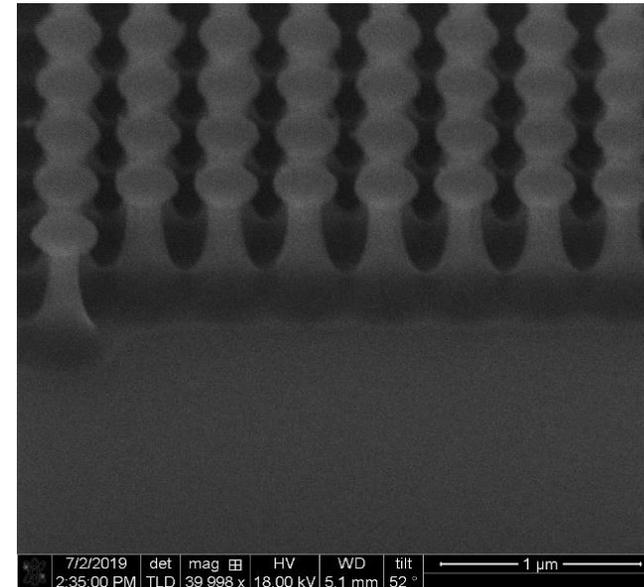
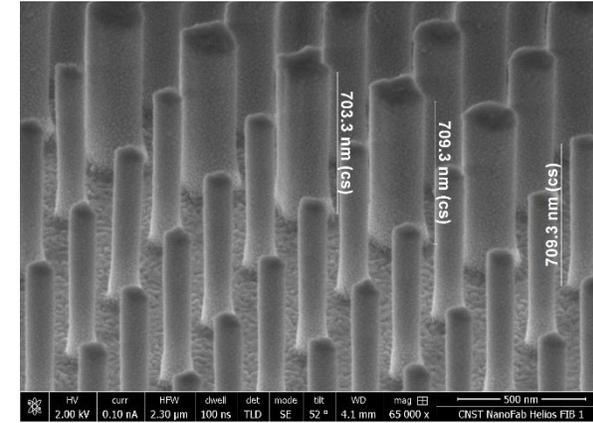
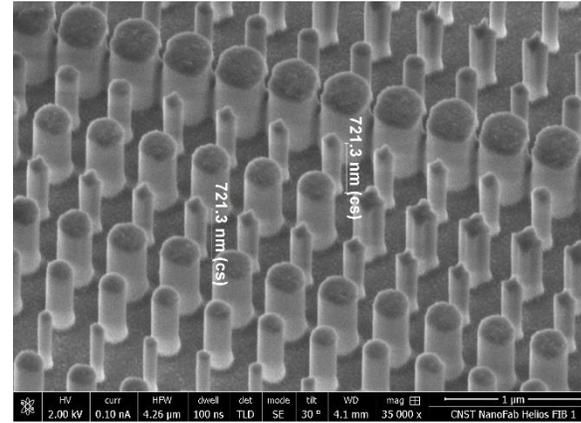
Planopsim supplies R&D tools to engineers & scientists that allow to unlock the maximum benefit of flat optics in a user-friendly way.

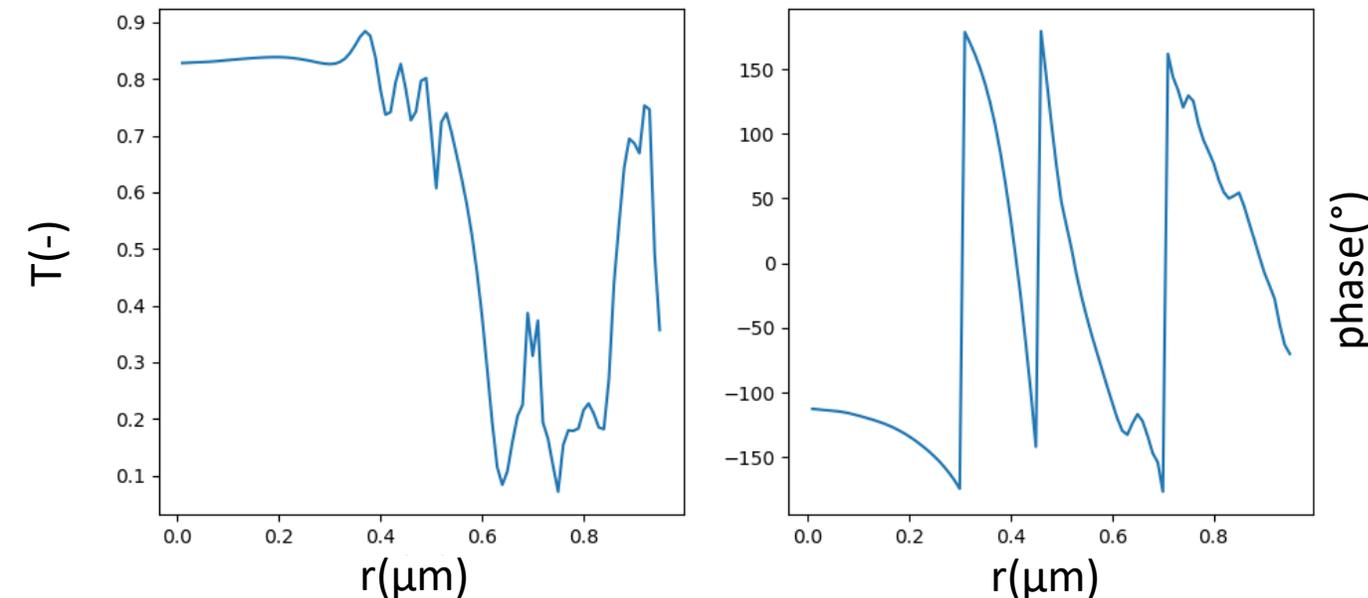
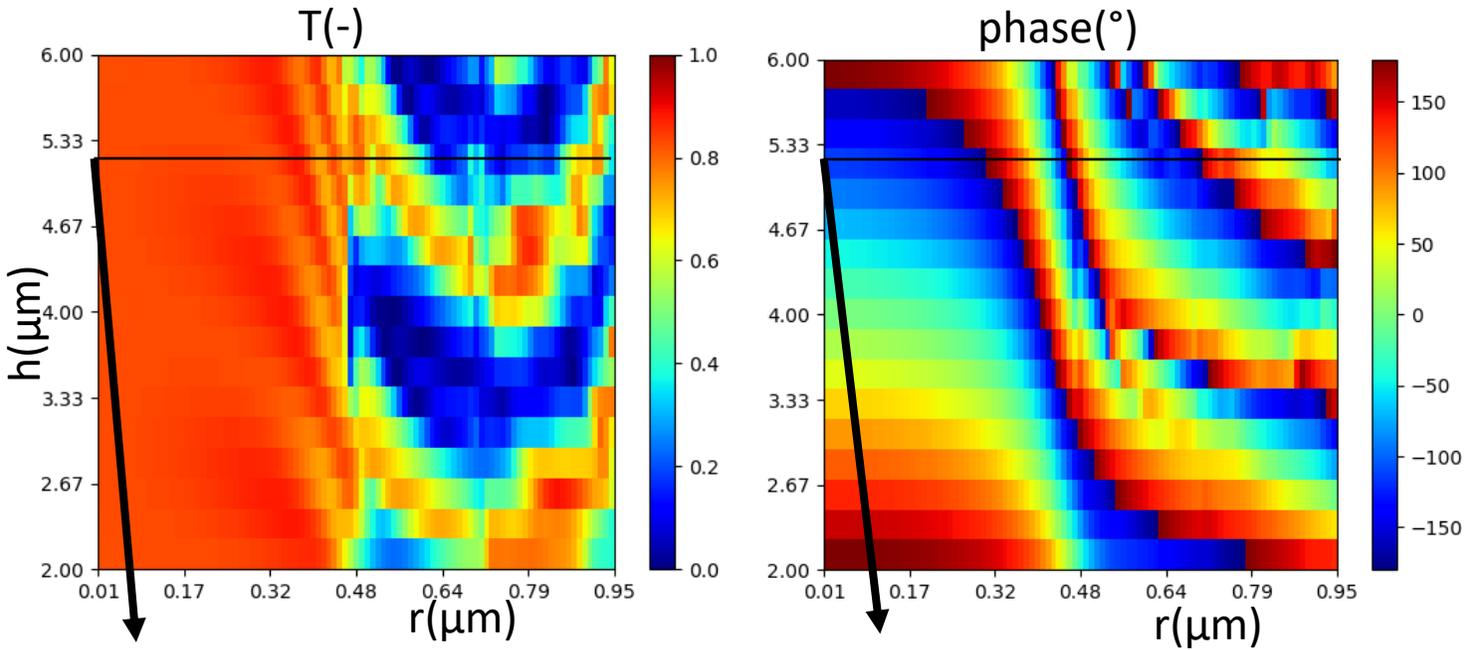
- ❖ Computer Aided Design software for Planar Optics & metasurfaces
  - All-in-one design workflow
- ❖ Design service for metasurfaces and photonics
  - In-house and 3<sup>d</sup> party tools



# Which errors are critical?

- ❖ Typical design assumption:
  - All structures are perfect
  - Optimize until specification is reached
- ❖ **X Million structures** in 1 meta-surface component
- ❖ There are systematic & random errors
  - This study: **systematic errors**
  - Random errors: Monte Carlo analysis
- ❖ In practice:
  - Which errors are critical-to-quality?
  - What is the effect of various error types
  - Which deviation can be tolerated of each type
- ❖ Sensitivity analysis:
  - Design using nominal structures
  - Simulation replaces nominal by perturbed structures





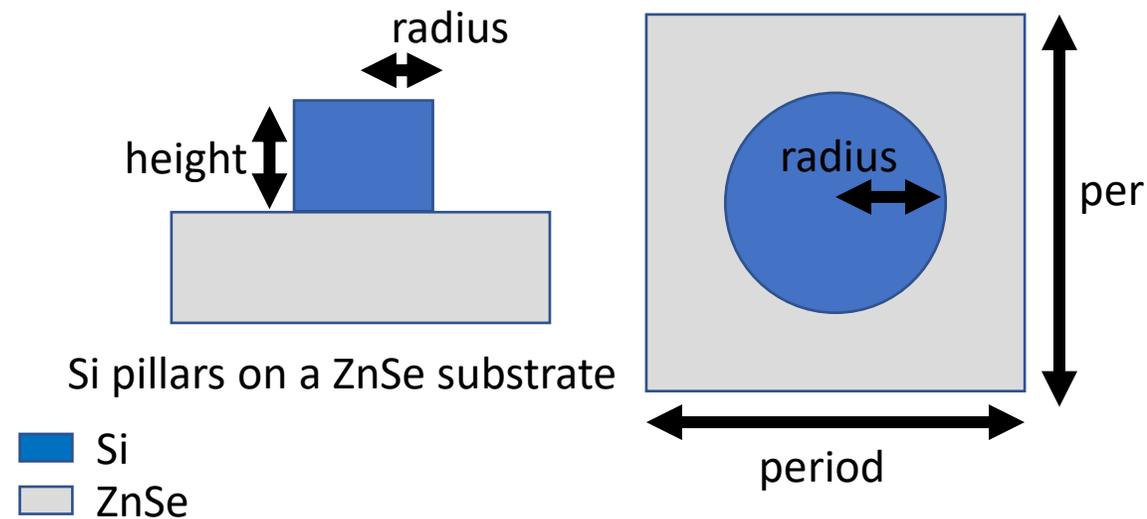
## ❖ Meta-atom type:

- Design  $\lambda$ :  $4 \mu\text{m}$
- a-Si Cylindrical pillars on ZnSe
- Square arrangement

## ❖ Configurations scanned with full Maxwell solver (PlanOpSim MetaCell)

## ❖ 8 meta-atoms selected for $0-360^\circ$ phase coverage

- P:  $2 \mu\text{m}$
- H:  $5,25 \mu\text{m}$



## ❖ Reference lens parameters:

- Size: 10 x 10 mm
- Focal distance  $f$ : 20 mm
- Corresponding NA: 0.24

## ❖ Analytical spherical phasefront:

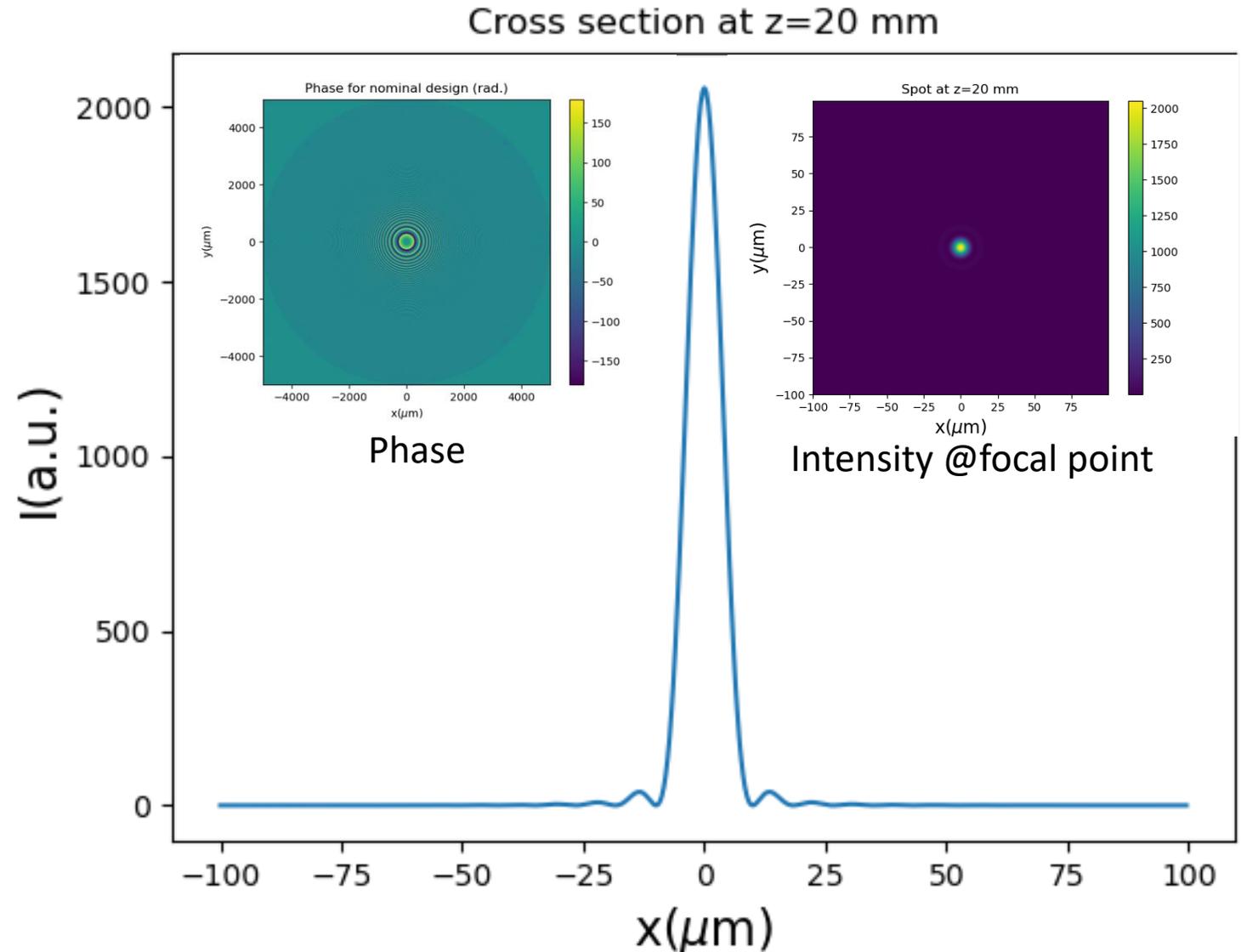
$$\varphi(\lambda) = \frac{2\pi}{\lambda} \left[ \sqrt{x^2 + y^2 + f^2} - f \right]$$

## ❖ Simulated using:

- Fresnel propagation
- Local periodic approximation
- PlanOpSim Meta-Component

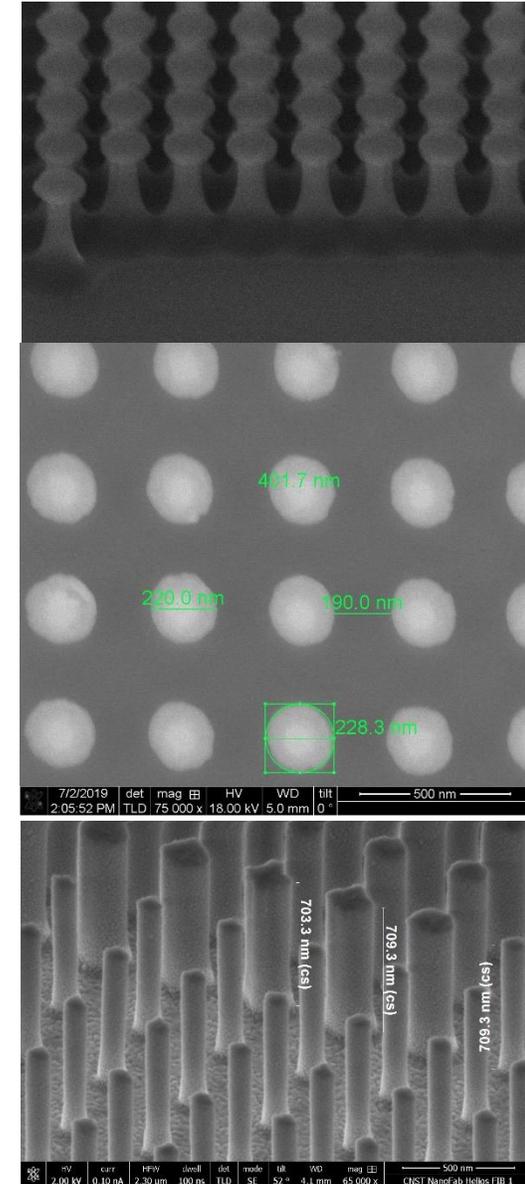
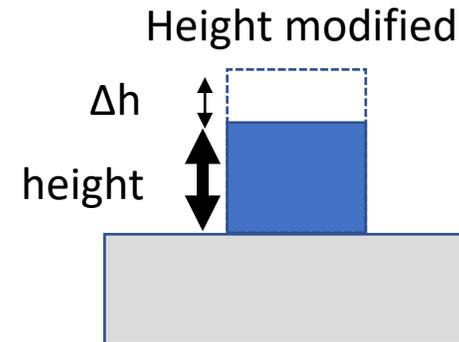
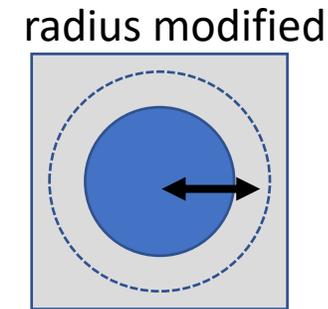
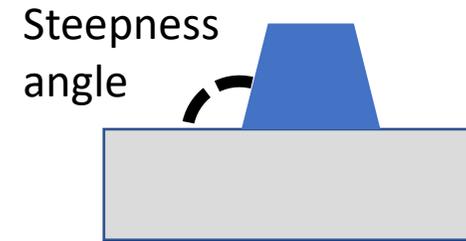
## ❖ Nominal spot characteristics:

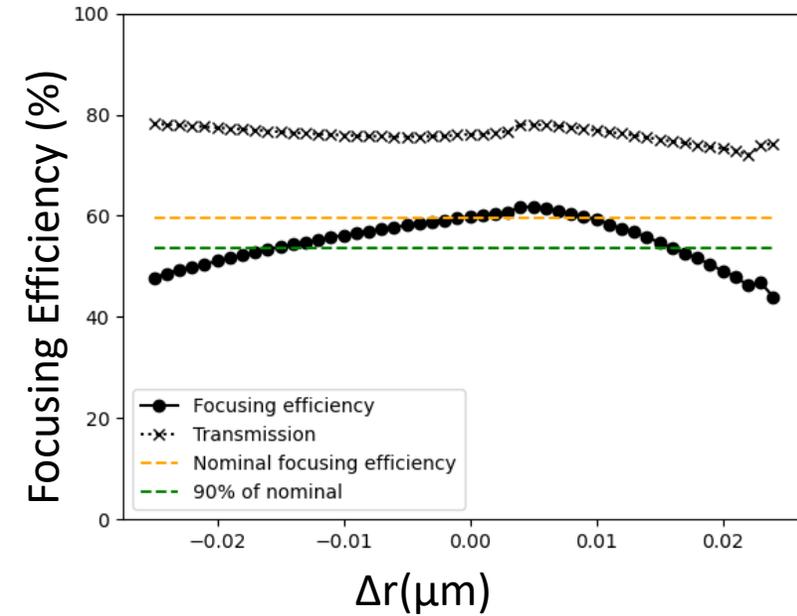
- FWHM: 8.43  $\mu\text{m}$
- Transmission efficiency: 76.0%
- Focussing efficiency: 59%



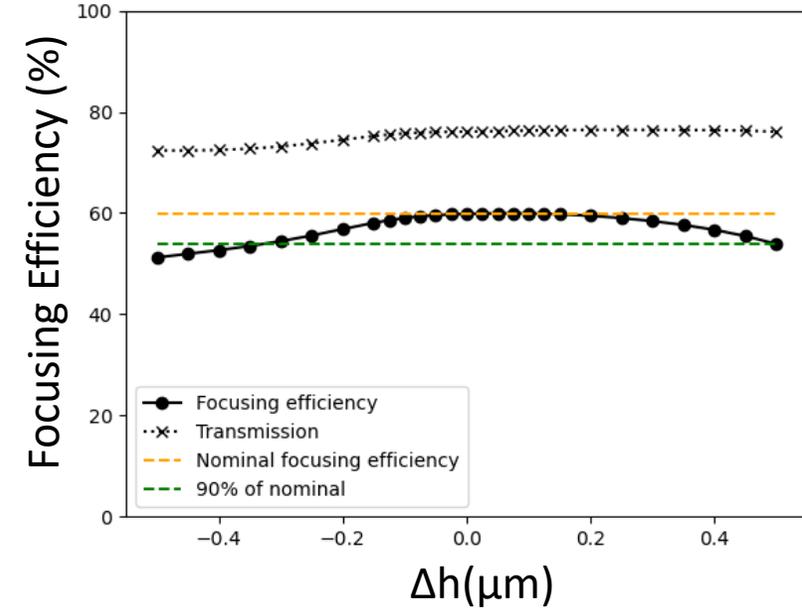
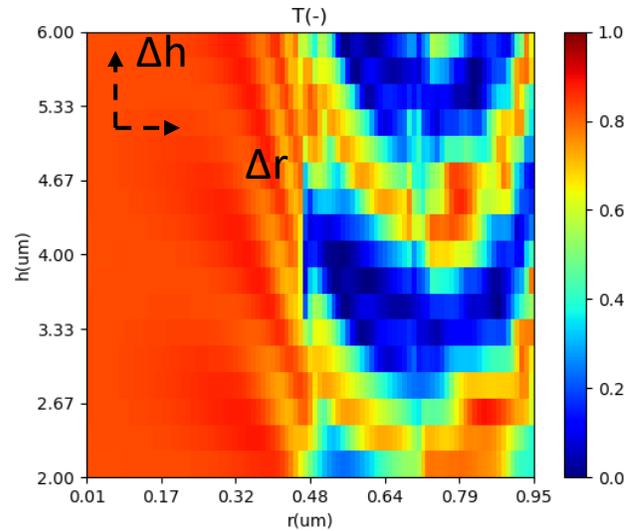
# Error types

- ❖ Meta-atoms **uniformly modified from nominal** design parameters over entire meta-lens
- ❖ Sidewall angle
  - Nominally  $90^\circ$
  - Varied parameter: angle
  - Assumption: cylinder  $\rightarrow$  cone
  - Over- and underetching common
- ❖ Direct radius deformation
  - Varied parameter:  $\Delta r$
  - Differences in resist exposure/developing
- ❖ Height difference
  - Varied parameter:  $\Delta h$
  - Variations in film evaporation
- ❖ There are many more!

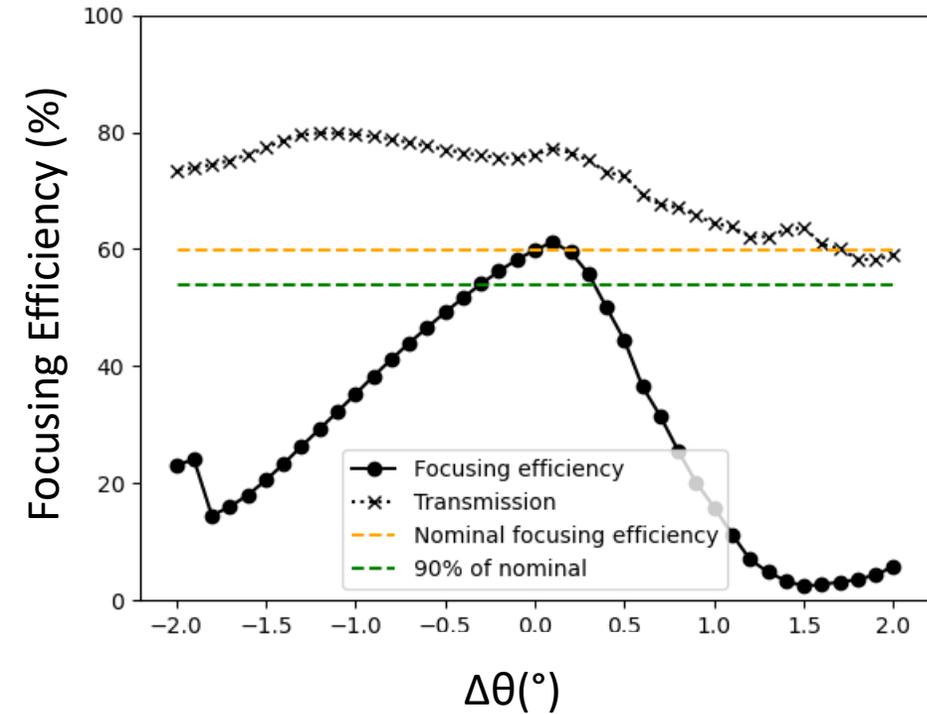




- ❖  $\Delta r = \pm 0,025 \mu\text{m}$
- ❖ Transmission 76- $\rightarrow$  72%
- ❖ Focussing efficiency 59,9- $\rightarrow$ 44,0%
- ❖ Threshold 90% of nominal focussing efficiency:
  - $\pm 15\text{nm}$
  - 0,75% of pitch/ 0,375%  $\lambda$

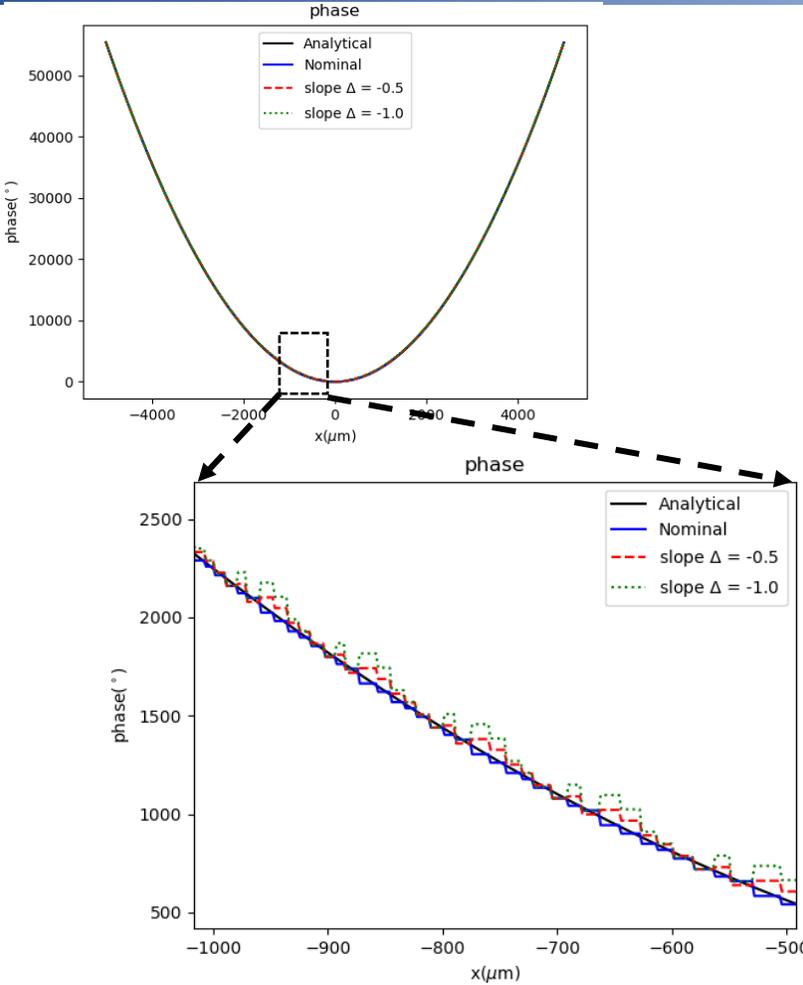


- ❖  $\Delta h = \pm 0,50 \mu\text{m}$
- ❖ Transmission 76- $\rightarrow$  72,3%
- ❖ Focussing efficiency 59,9- $\rightarrow$ 51,2%
- ❖ Threshold 90% of nominal focussing efficiency:
  - -300nm+500nm
  - -5,7/+9,5% of height
  - -7,5% / 12,5%  $\lambda$



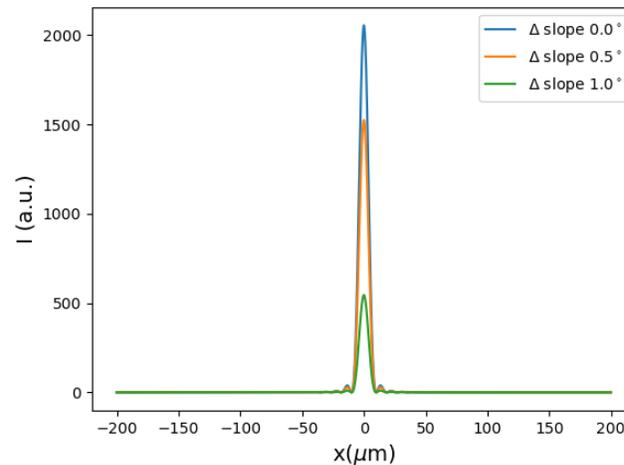
- ❖  $\Delta\theta = \pm 2^\circ$
- ❖ Most sensitive parameter
- ❖ Transmission 76  $\rightarrow$  58.2%
- ❖ Focussing efficiency 59,9  $\rightarrow$  2.4%
- ❖ Focussing reduces more quickly than transmission
- ❖ Threshold 90% of nominal focussing efficiency:
  - $\pm 0,3^\circ$

# What causes the performance loss

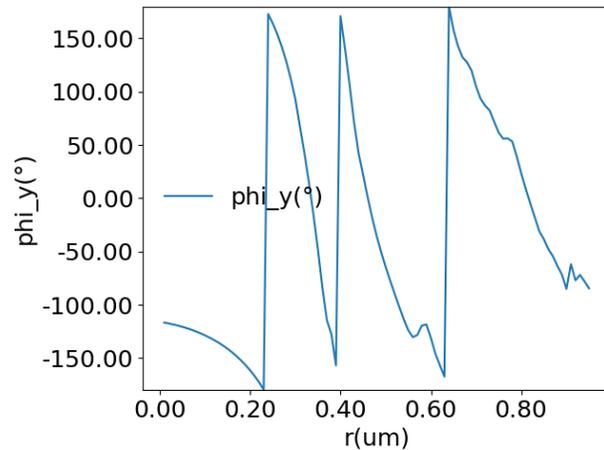
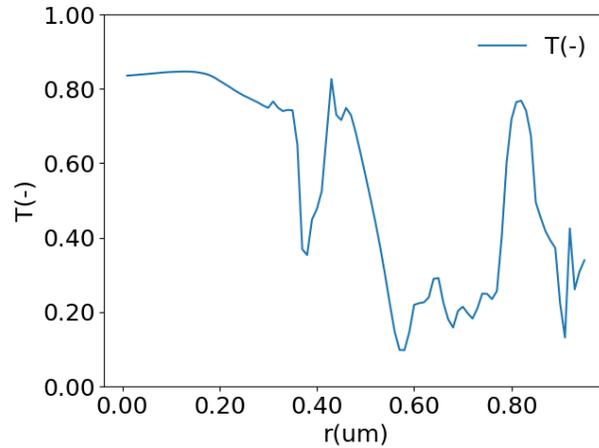


- ❖ Wavefront phase for nominal and aberrated cases
  - Example: sidewall angle
- ❖ Overall wavefront shape remains the same
- ❖ Aberrated wavefront -> perturbation on ideal wavefront
  - Focal distance remains the same
  - Spot width remains the same
  - Loss of efficiency to scattering
- ❖ Transmission: additional loss

Intensity at z = 20mm



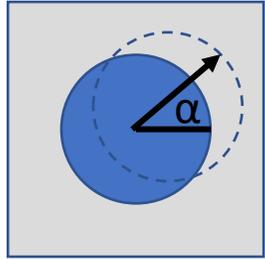
Sidewall angle	Phase error (RMS)	Amplitude error (RMS)
90° (nominal)	16,2°	0,19
89,5°	34,2°	0,23
89°	68,5°	0,35



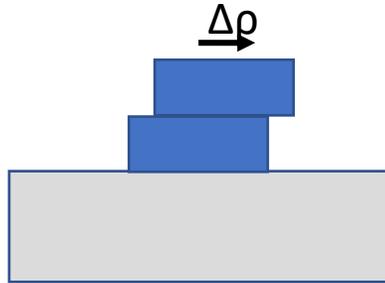
- ❖ Known sidewall steepness  $88,5^{\circ}$  (worst case)
- ❖ Meta-atoms resimulated and selected
  - $P = 2\mu\text{m}$
  - $H = 5,25\mu\text{m}$
- ❖ Meta-atoms placement repeated using new meta-atom results
- ❖ **A known and constant error can be compensated**

Sidewall angle	Transmission	Focussing efficiency	F/T
<b>90° (nominal)</b>	<b>76%</b>	<b>59.9%</b>	<b>0,76</b>
88,5° (uncompensated)	63,7%	2,4%	0,04
<b>88,5° (compensated)</b>	<b>76,7%</b>	<b>60,9%</b>	<b>0,79</b>

Top view



Side view



- ❖ Multi-layer structures

- Reference case 2-layers

- ❖ Alignment error:

- Angle  $\alpha$  (0-90°)
- Distance  $\rho$  (0-325nm)

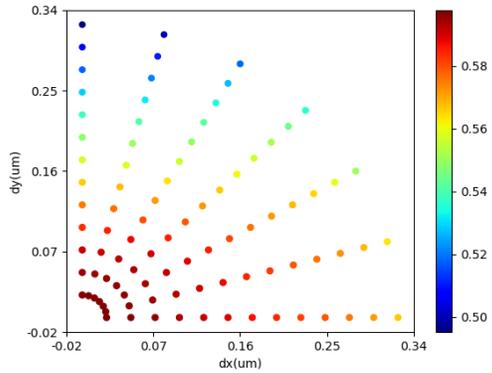
- ❖ Average focussing independent of angle

- Causes polarization sensitivity

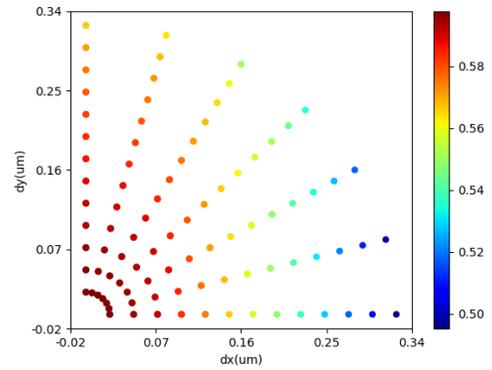
- ❖ Focusing efficiency 59.9->53,1%

- Transmission 76% -> 70,1%
- Efficiency mostly lost through reduced transmission

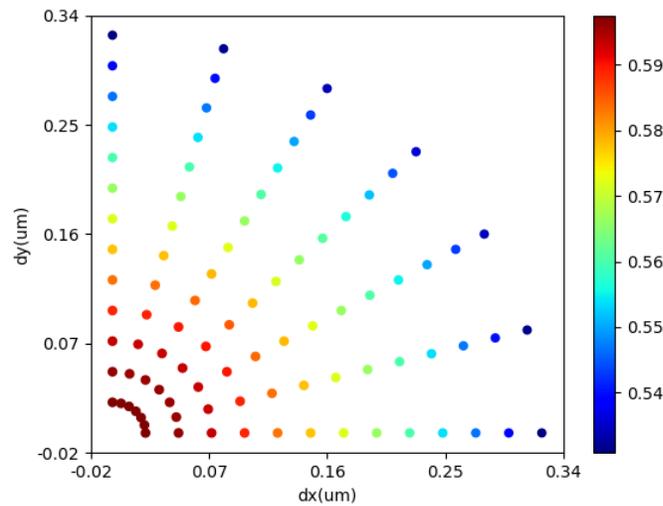
TE



TM



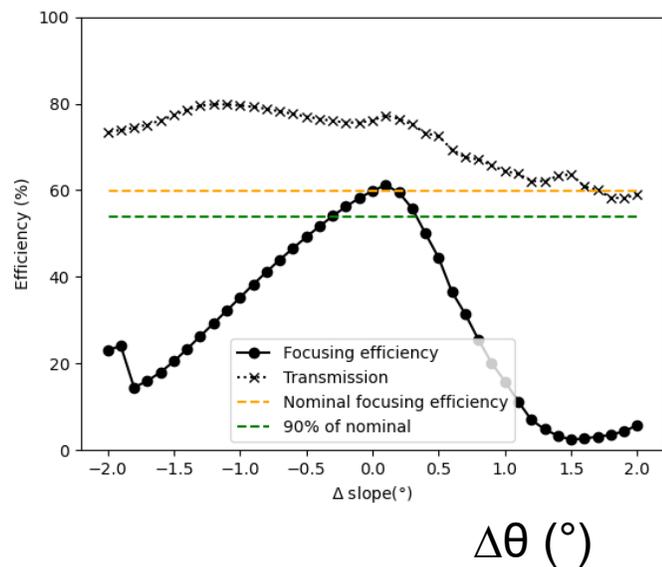
Focussing Efficiency



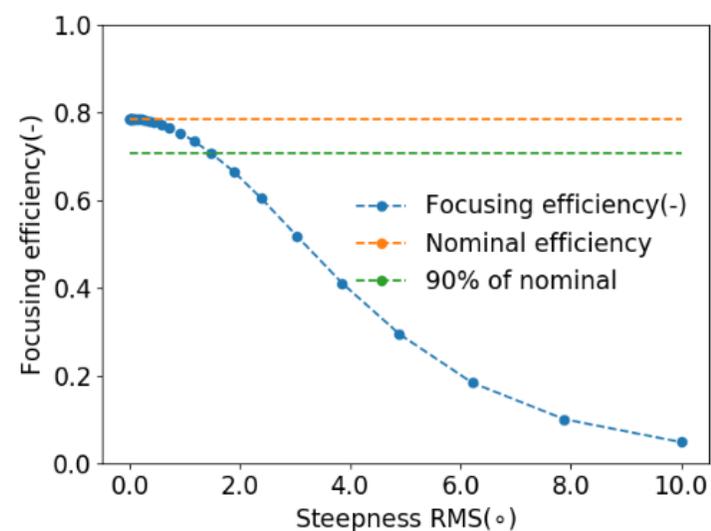
# Comparison systematic to random error

- ❖ Systematic errors have a stronger impact than random errors on focussing efficiency
- ❖ Monte carlo results for meta-lens for 532nm

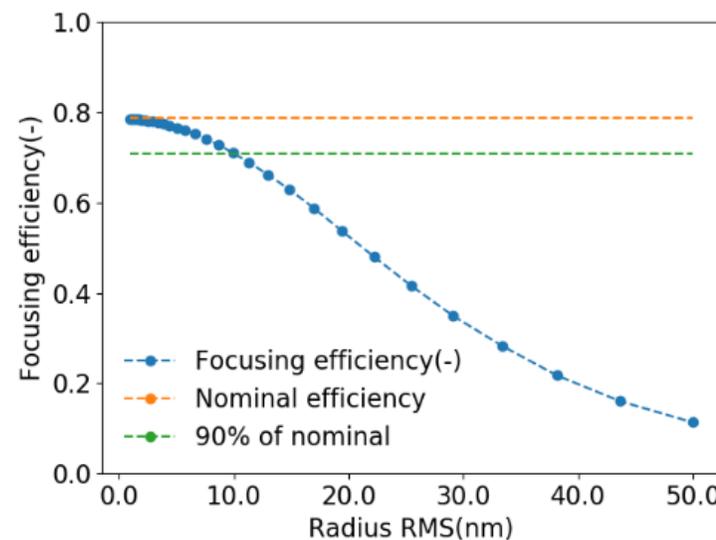
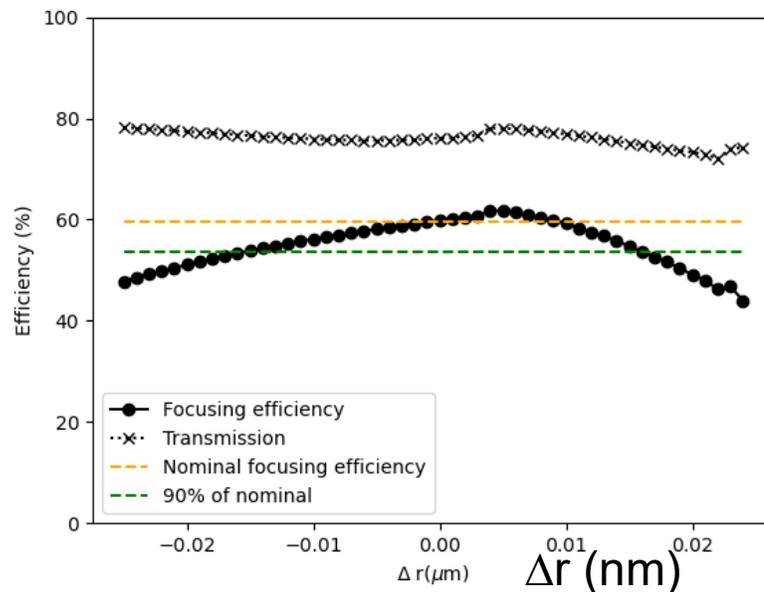
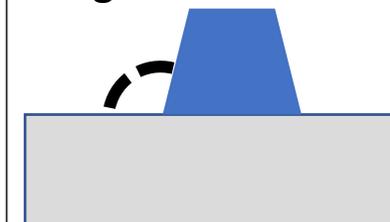
### Systematic errors



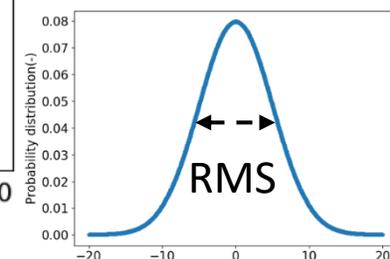
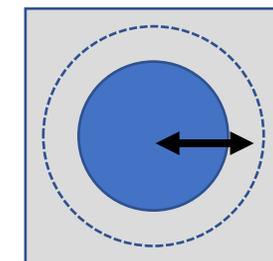
### Random errors (Monte Carlo)



Steepness angle



radius modified



- ❖ **Knowing and controlling critical parameters** is crucial
- ❖ **Sensitivity analysis** used to **identify** critical parameters and **quantify tolerance criteria**
- ❖ Fast integrated **simulations** provide insight to the **link** between structural **parameters** and device **performance**
- ❖ **Wavefront aberration** is the main cause of efficiency loss
- ❖ Fabrication guidelines (for reference metalens)

Parameter	Tolerance for 90% of nominal efficiency
Sidewall slope	$\pm 0,3^\circ$
Radius	$\pm 15\text{nm}$ (0,75% of pitch)
Height	$-300\text{nm}/+500\text{nm}$ (5,7/9,5% of height)

Reach us here!

 [www.planopsim.com](http://www.planopsim.com)

 [lieven.penninck@planopsim.com](mailto:lieven.penninck@planopsim.com)

 +32 485 56 57 72

Supported by:

 **imec** istart

 **AGENTSCHAP  
INNOVEREN &  
ONDERNEMEN**

With the support of

**FLANDERS  
INVESTMENT &  
TRADE**



FLANDERSINVESTMENTANDTRADE.COM